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Terms	Documents
L3 and (evacuato\$ same (reactor or chamber))	56

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<u>L4</u>	L3 and (evacuato\$ same (reactor or chamber))	56	<u>L4</u>
<u>L3</u>	L2 and (flux near\$ electron)	177	<u>L3</u>
<u>L2</u>	L1 and (CVD or chemical vapor deposition)	51188	<u>L2</u>
<u>L1</u>	(438/\$ OR 427/\$ OR 118/\$).CCLS.	320658	<u>L1</u>

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